

METHOD OF CONTROLLING LINE EDGE ROUGHNESS IN RESIST FILMS

ABSTRACT OF THE DISCLOSURE

Disclosed is a method of forming an integrated circuit line on a wafer using a lithographic technique. The method can include forming a photo resist line
5 having a line width smaller than a desired line width of the integrated circuit line. The photo resist line can be reacted with a coating to form a mask line having a line width corresponding to the desired line width of the integrated circuit line and with a smaller line edge roughness (LER) than of the photo resist line.

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